

**REMARKS**

At the outset, the Examiner is thanked for the thorough review and consideration of the pending application. The final Office Action dated October 14, 2005, has been received and its contents carefully reviewed.

Claims 14-21 are withdrawn in this application. Claims 1, 2 and 5-11 are rejected and claims 3, 4, 12 and 13 are objected to by the Examiner. Claims 1-21 remain pending in this application.

In the Office Action, claims 1, 6-9 and 11 are rejected under 35 U.S.C. § 103(a) as being unpatentable over U.S. Patent No. 6,407,784 B1 to Kanou et al. (hereinafter "Kanou '784") in view of U.S. Patent No. 6,784,957 B2 to Kanou et al. (hereinafter "Kanou '957"). Claims 2, 5 and 10 are rejected under 35 U.S.C. § 103(a) as being unpatentable over Kanou '784 and Kanou '957 as applied in claims 1, 6-9 and 11, and further in view of applicant's related art (ARA).

The rejection of claims 1, 6-9, and 11 is respectfully traversed and reconsideration is requested. Claims 1, 6-9, and 11 are allowable over the cited references in that each of these claims recites a combination of elements including, for example, "forming a first peak and depression layer in the first organic insulating layer by using a first mask," and "forming a second peak and depression layer in the second organic insulating layer by using a second mask." None of the cited references including Kanou '784 or Kanou '957, singly or in combination, teaches or suggests at least this feature of the claimed invention.

In the Office Action, the Examiner states that Kanou '784 discloses: "forming a first raised and recessed (peak and depression) layer (25) in the first insulating layer (28)"; and "forming second raised and recessed (peak and depression) layer (25A) in second insulating film (30)." Kanou '784 is directed to a reflective liquid crystal display. Projections 73 may be formed from the various layers used to form the thin film transistor. The top most layer of the projection being the first insulating film 28. (See col. 9, ll. 18-23.) Next a second insulating film 30 is deposited over the first insulating film 28 forming the first raised and recessed portions 25. The second raised and recessed portions 25A are then formed when the light-reflective electrode plate 74 is formed over the second insulating film 30. The insulating film 30 does not need to be formed using a mask, because the insulating film 30 is deposited over the pillar-shaped projections 72 resulting in the raised and recessed portions 25.

The Examiner admits that Kanou '784 does not disclose using first and second masks to form the first and second peak and depression layers. In order to cure this deficiency, the Examiner cites Kanou '957 as teaching the use of masks in the formation of convex/concave patterns in an insulating film. While such a mask may be used in forming the projections 73 using the photolithography and etching steps that form the thin film transistor, no such mask is contemplated in the formation of the first raised and recessed portions 25 formed when the second insulating film 30 is deposited over the projections 73. It is not necessary, because when the second insulating film 30 is deposited over the projection 73, the desired raised and recessed portions result. In actuality, this teaches away from the need for a second mask pattern, as simply depositing the second insulating film over the projections 73 achieves the desired shape. Further, in Kanou '784 a single raised and recessed pattern is built up from placing layers over the projections 73. In the present invention, the final pattern of the reflective electrode results from the combination of two different patterns formed with the different masks on the two insulating layers.

Further, nowhere does the Examiner explicitly address where using a second mask to form a second peak and depression layer is disclosed in the cited references. As pointed out above Kanou '784 clearly teaches away from needing a second mask because the second insulating film 30 forms the desired shape when deposited. The present invention teaches using a second mask to achieve the desired shape. Applicant's respectfully request, if the rejection is maintained, that the Examiner more clearly show where the cited references teach this feature of the claimed invention.

Accordingly, Applicant respectfully submits that claims 1, 6-9, and 11 are allowable over the cited references.

Claims 2, 5, and 10 depend from allowable claim 1 because the additionally cited ARA does not cure the deficiencies of Kanou '784 and Kanou '957 identified above.

Applicants believe the foregoing remarks place the application in condition for allowance and early, favorable action is respectfully solicited.

If for any reason the Examiner finds the application other than in condition for allowance, the Examiner is requested to call the undersigned attorney at (202) 496-7500 to discuss the steps

necessary for placing the application in condition for allowance. All correspondence should continue to be sent to the below-listed address.

If these papers are not considered timely filed by the Patent and Trademark Office, then a petition is hereby made under 37 C.F.R. § 1.136, and any additional fees required under 37 C.F.R. § 1.136 for any necessary extension of time, or any other fees required to complete the filing of this response, may be charged to Deposit Account No. 50-0911. Please credit any overpayment to deposit Account No. 50-0911. *A duplicate copy of this sheet is enclosed.*

Respectfully submitted,

Dated: January 10, 2006

By

  
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